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THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

**YASUMOTO, Tamihide**

Group Art Unit: 2813

Serial No.: 09/995,575 ✓

Examiner: KIELIN, E.

Filed: November 29, 2001 ✓

P.T.O. Confirmation No.: 1497

For. **SEMICONDUCTOR DEVICE MANUFACTURING METHOD USING METAL SILICIDE REACTION AFTER ION IMPLANTATION IN SILICON WIRING**

**PETITION FOR EXTENSION OF TIME**

Commissioner for Patents  
Washington, D.C. 20231

Date: February 5, 2003

Sir:

Applicants petition the Commissioner for Patents to extend the time for response to the Office Action dated September 24, 2002 for two months from December 24, 2003 to February 24, 2003.

Attached please find a check in the amount of \$410.00 to cover the cost of the extension for a large entity. In the event that any additional fees are due in connection with this paper, please charge our Deposit Account No. 01-2340.

Respectfully submitted,

ARMSTRONG, WESTERMAN & HATTORI, LLP

*Sadao Kinashi*

Sadao Kinashi  
Attorney for Applicant  
Reg. No. 48,075

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Atty. Docket No. 011317  
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PATENT TRADEMARK OFFICE